Minutes from OpenPICs WP 4 meeting 12-06-2017

Present: Longfei, Rui, Rob, Roel, Steven, Rene, Robert, Weiming, Kevin

Discussion/action points

Nr.	Description	Responsible
1.	**Al-MQW** • The design will be ready in 1-2 weeks. • The Al-Q will be calibrated in both Nanolab and Smart reactors.	Weiming, Longfei
2.	**Zn diffusion tests** • Reactor down, supplier needs to find a replacement part. We will be kept updated on a daily basis. • Quick diffusion test on a SiO2 mask covered sample. • Get an empirical model based on more data points with the standard MPW layerstack. • 4 samples will be shipped to UK for SIMS measurement. • Check the SiNx mask covered sample. • Test with mask opening. Longfei will follow up on the design.	Rene Longfei
3.	**BCB planarization** • Planarization test has been done on the sample from Smart. Tencor is back from supplier, needs to be set up and calibrated (this week by Barry). • Lithography parameters have to be re-optimized for BCB.	Tjibbe
4.	**Stepper process** • First FEM tests with AZ resist done. Optimal focus range found. Next: tune the energy to get the same CD as in the MA6 process. • Test with MaN resist. Cross-section SEM can be done in July-August by an internship student.	Robert
5.	**Etching process** • The new CH4-H2 recipe (optimized for ~3 degree side-wall angle in Smart's ICP) will be transferred to Nanolab after a few more fine-tuning. • Regarding the Cl2-CH4-H2 recipe, Oxford suggested to increase the H2 flow and RF power. Longfei will prepare a new batch of wafers for the next test.	Rui Longfei
6.	**Planning and milestone list** The milestone list with quantified criteria has been sent around. Each responsible person should check their own items. Upcoming due dates for milestones: M 3.1 (end June) Zn-diffusion time determined: ready for joint MPW validation. M 5.1 (end June) DUV lithography introduced to MPW.	Everyone Rene Smart

Next meeting: 13:30-15:00, 26-6-2017, Flux 10.177